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Sequential deposition of patterned porous polymers using poly(dimethylsiloxane) masks

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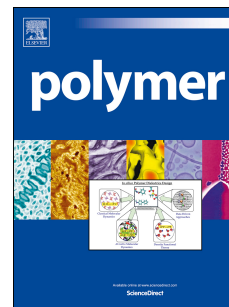
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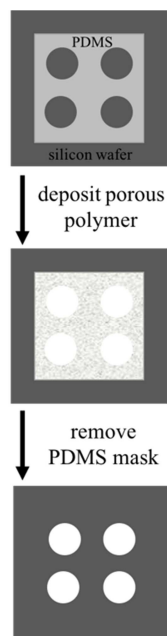
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